

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	75	marangoni and megaso\$	USPAT	OR	OFF	2004/12/10 12:26
L2	1	"6726848".pn.	USPAT	OR	OFF	2004/12/10 12:27
L3	9	("5017236" "5090432" "5601655" "6006765" "6192600" "6240938" "6273100" "6311702" "6328814").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/10 12:27
L4	0	("6726848").URPN.	USPAT	OR	OFF	2004/12/10 12:38
L5	1	"6726848"	DERWENT	ADJ	OFF	2004/12/10 13:33

DERWENT-ACC-NO: 2003-523443

DERWENT-WEEK: 200466

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TITLE: Treatment of substrates by enclosing one or two substrates within process chamber, exposing substrates to first process fluid, then exposing substrates to second process fluid

INVENTOR: BLECK, M; HANSEN, E ; MIMKEN, V ; ROSATO, J ; YALAMANCHILI, R M ; YALAMANCHILI, M R

PATENT-ASSIGNEE: SCP GLOBAL TECHNOLOGIES INC[SCPGN] , BLECK M[BLECI], HANSEN E[HANSI], MIMKEN V[MIMKI], ROSATO J[ROSAI], YALAMANCHILI M R[YALAI]

PRIORITY-DATA: 2001US-0010240 (December 7, 2001) , 2004US-0826458 (April 16, 2004)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE
PAGES MAIN-IPC		
US 20040198051 A1	October 7, 2004	N/A
000 H01L 021/302		
WO 2003050861 A1	June 19, 2003	E
075 H01L 021/306		
US 20030205559 A1	November 6, 2003	N/A
000 C23F 001/00		
AU 2002362092 A1	June 23, 2003	N/A
000 H01L 021/306		
US <u>6726848</u> B2	April 27, 2004	N/A
000 H01L 021/00		
EP 1454350 A1	September 8, 2004	E
000 H01L 021/306		

DESIGNATED-STATES: AE AG AL AM AT AU AZ BA BB BG BR BY BZ CA CH CN CO CR CU CZ DE DK DM DZ EC EE ES FI GB GD GE GH GM HR HU ID IL IN IS JP KE KG KP KR KZ LC LK LR LS LT LU LV MA MD MG MK MN MW MX MZ NO NZ OM PH PL PT RO RU SD

SE SG SK
 SL TJ TM TN TR TT TZ UA UG US UZ VN YU ZA ZM ZW AT BE BG CH CY CZ DE
 DK EA EE
 ES FI FR GB GH GM GR IE IT KE LS LU MC MW MZ NL OA PT SD SE SI SK SL
 SZ TR TZ
 UG ZM ZW AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR IE IT LI LT LU
 LV MC MK
 NL PT RO SE SI SK TR

APPLICATION-DATA:

PUB-NO	APPL-DESCRIPTOR	APPL-NO
APPL-DATE		
US20040198051A1	Cont of	2001US-0010240
December 7, 2001		
US20040198051A1	N/A	2004US-0826458
April 16, 2004		
US20040198051A1	Cont of	US <u>6726848</u>
N/A		
WO2003050861A1	N/A	2002WO-US39174
December 6, 2002		
US20030205559A1	N/A	2001US-0010240
December 7, 2001		
AU2002362092A1	N/A	2002AU-0362092
December 6, 2002		
AU2002362092A1	Based on	WO2003050861
N/A		
US 6726848B2	N/A	2001US-0010240
December 7, 2001		
EP 1454350A1	N/A	2002EP-0797224
December 6, 2002		
EP 1454350A1	N/A	2002WO-US39174
December 6, 2002		
EP 1454350A1	Based on	WO2003050861
N/A		

INT-CL (IPC): B08B003/00, B08B003/000 , B44C001/22 , C03C015/00 ,
 C03C025/68 , C23F001/00 , C25F003/00 , H01L021/00 , H01L021/302 ,
 H01L021/306 , H01L021/461

ABSTRACTED-PUB-NO: WO2003050861A

BASIC-ABSTRACT:

NOVELTY - Substrates are individually treated by:

(a) providing a process chamber proportioned to enclose not more than two substrates at a time and enclosing one or two substrates within the process

chamber;

(b) exposing the substrates to a first process fluid within the process chamber; and

(c) exposing the substrate to a second process fluid within the process chamber.

DETAILED DESCRIPTION - An INDEPENDENT CLAIM is also included for a substrate treatment apparatus comprising a process chamber, a source of first process fluid coupled to the process chamber and a source of second process fluid coupled to the process chamber.

USE - Used for individually treating substrates.

ADVANTAGE - The process enables higher precision processing compared to batch processing. Each substrate is exposed to process fluids for a shorter time than that which is required in batch processing.

DESCRIPTION OF DRAWING(S) - The figure shows a single substrate processing chamber.

Megasonic transducers 32a, 32b

CHOSEN-DRAWING: Dwg.1E/9

TITLE-TERMS: TREAT SUBSTRATE ENCLOSE ONE TWO SUBSTRATE PROCESS CHAMBER EXPOSE
SUBSTRATE FIRST PROCESS FLUID EXPOSE SUBSTRATE SECOND PROCESS FLUID

DERWENT-CLASS: L03 P43 P78 U11

CPI-CODES: L04-C07C1; L04-D03;

EPI-CODES: U11-C06A1B; U11-C07B;

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C2003-140943

Non-CPI Secondary Accession Numbers: N2003-415291

WEST Search History

DATE: Friday, December 10, 2004

<u>Hide?</u>	<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>
		<i>DB=USPT; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L3	L2 and wafer	74
<input type="checkbox"/>	L2	marangoni and megaso\$	75
<input type="checkbox"/>	L1	marangoni nad megaso\$	0

END OF SEARCH HISTORY

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Fr
D
12PALM INTRANETTi
14**Inventor Name Search Result**

Your Search was:

Last Name = CAWLFIELD

First Name = B.

Application#	Patent#	Status	Date Filed	Title	Inventor Name 4
10064571	Not Issued	030	07/26/2002	MEGASONICALLY ENERGIZED LIQUID INTERFACE APPARATUS AND METHOD	CAWLFIELD, B. GENE
08417462	Not Issued	161	04/05/1995	CONTROLLED FLUID AGITATION METHOD AND APPARATUS	CAWLFIELD , B. GENE
08120598	Not Issued	161	09/13/1993	CONTROLLED FLUID AGITATION METHOD AND APPARATUS	CAWLFIELD , B. GENE
07676272	5246025	150	03/28/1991	CONTROLLED FLUID AGITATION METHOD AND APPARATUS	CAWLFIELD , B. GENE

Inventor Search Completed: No Records to Display.**Search Another:
Inventor**

Last Name

First Name

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